

Title (en)
AQUEOUS POLISHING COMPOSITION AND PROCESS FOR CHEMICALLY MECHANICALLY POLISHING SUBSTRATES CONTAINING SILICON OXIDE DIELECTRIC AND POLYSILICON FILMS

Title (de)
WÄSSRIGE POLIERZUSAMMENSETZUNG UND VERFAHREN ZUM CHEMISCH-MECHANISCHEN POLIEREN VON SUBSTRATEN MIT DIELEKTRISCHEN SILICIUMOXID- UND POLYSILICIUMFILMEN

Title (fr)
COMPOSITION DE POLISSAGE AQUEUSE ET PROCÉDÉ DE POLISSAGE MÉCANO-CHIMIQUE DE SUBSTRATS CONTENANT UN DIÉLECTRIQUE EN OXYDE DE SILICIUM ET DES FILMS EN POLYSILICIUM

Publication
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Application
EP 11846454 A 20111207

Priority
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Abstract (en)
[origin: WO2012077063A1] An aqueous polishing composition comprising (A) abrasive ceria particles and (B) amphiphilic nonionic surfactants selected water-soluble and water-dispersible, linear and branched polyoxyalkylene blockcopolymers of the general formula I: R[(B1)^m/(B2)ⁿY]^p (I), wherein the indices and the variables have the following meaning: m, n, and p integers = 1; R hydrogen atom or monovalent or polyvalent organic residue, except C5-C20 alkyl groups; (B1) block of oxyethylene monomer units; (B2) block of substituted oxyalkylene monomer units wherein the substituents are selected from two methyl groups, alkyl groups of more than two carbon atoms and cycloalkyl, aryl, alkyl-cycloalkyl, alkyl-aryl, cycloalkyl-aryl and alkyl-cycloalkyl-aryl groups; and Y hydrogen atom or monovalent organic residue, except C5-C20 alkyl groups; with the proviso that when (B) contains more than one block (B1) or (B2) two blocks of the same type are separated by a block of the other type.

IPC 8 full level
C09G 1/02 (2006.01); **C09K 3/14** (2006.01); **H01L 21/321** (2006.01)

CPC (source: EP KR US)
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Citation (search report)
• [ID] US 2007077865 A1 20070405 - DYSARD JEFFREY M [US], et al
• [AD] JP 2001240850 A 20010904 - SANYO CHEMICAL IND LTD
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• See references of WO 2012077063A1

Designated contracting state (EPC)
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